## LISTING OF CLAIMS

- 1. (Currently Amended) A polishing pad comprising:
  a polishing body comprising a material wherein said material is a cross-linked polymer having a
  hardness ranging from about 34 Shore A to about 60 Shore A.
- 2. (Original) The polishing pad as recited in Claim 1 wherein said cross-linked polymer is a thermoplastic foam.
- 3. (Original) The polishing pad as recited in Claim 1 wherein said cross-linked polymer has a closed cell structure.
- 4. (Original) The polishing pad as recited in Claim 3 wherein said cross-linked polymer is polyethylene.
- 5. (Original) The polishing pad as recited in Claim 1 wherein said polishing body includes a base pad and said cross-linked polymer forms a polishing surface located over said base pad.
- 6. (Original) The polishing pad as recited in Claim 1 wherein said cross-linked polymer is a polyethylene having a closed cell structure.

Claim 7 (Canceled without prejudice or disclaimer)

8. (Original) The polishing pad as recited in Claim 1 wherein said cross-linked polymer has a selectivity of Cu to Ta removal rates of greater than about 27:1.

Claims 9-27 (Canceled without prejudice or disclaimer).